

IN THE CLAIMS:

Please amend claims 19-24 as follows. Note that all the claims currently pending in this application, including those not presently being amended, have been reproduced below for the Examiner's convenience.

1-18. (Cancelled)

19. (Currently Amended) An exposure apparatus comprising:

a chuck for holding an object; and

an optical system for directing light from a light source to the object held by said chuck, said optical system including a multilayer film mirror which has a concave reflecting surface,

wherein an area of contacting portions of said chuck is set so that the ~~contact~~ contacting portions area of the chuck is at most 10% of an area of the object held by said chuck.

20. (Currently Amended) An exposure apparatus according to claim 19, wherein the area of contacting portions of said chuck is set to so that the ~~contact portions~~ contacting portions area of the chuck is at most 2% of the area of the object held by said chuck.

21. (Currently Amended) A device manufacturing method using an exposure apparatus that includes (i) a chuck for holding an object, and (ii) an optical system for directing light from a light surface to the object held by said chuck, said optical system including a

multilayer film mirror which has a concave reflecting surface, wherein an area of contacting portions of said chuck is set so that the ~~contact~~ contacting portions area of the chuck is at most 10% of an area of the object hold by said chuck, said method comprising the steps of:

holding the object by the chuck; and

directing the light to the object using the optical system.

22. (Currently Amended) An exposure apparatus comprising:

an illumination system for illuminating a reflection mask with light from a light source, said illumination system including a multilayer film mirror which has a concave reflecting surface;

a projection optical system for projecting a pattern of the reflection mask onto an object; and

a mask chuck for holding the reflection mask,

wherein an area of contacting portions of said mask chuck is set so that the ~~contact~~ contacting portions area of the mask chuck is at most 10% of an area of the reflection mask held by said mask chuck.

23. (Currently Amended) An exposure apparatus according to claim 22, wherein the area of contacting portions of said mask chuck is set so that the ~~contact~~ contacting portions area of the mask chuck is at most 10% of the area of the reflection mask held by said mask chuck.

24. (Currently Amended) A device manufacturing method comprising the steps of:

exposing an object using an exposure apparatus; and

developing the object that has been exposed,

wherein the exposure apparatus includes:

an illumination system for illuminating a reflection mask with light from a light source, said illumination system including a multilayer film mirror which has a concave reflecting surface;

a projection optical system for projecting a pattern of the reflection mask onto the object; and

a mask chuck for holding the reflection mask,

wherein an area of contacting portions of the mask chuck is set so that the ~~contact~~ contacting portions area of the mask chuck is at most 10% of an area of the reflection mask held by the mask chuck.